

① 読みたい論文のページから「Access through your institution」をクリック

IOPscience Journals Books Publishing Support Login

Japanese Journal of Applied Physics

REGULAR PAPER

Ab initio study for orientation dependence of nitrogen incorporation at 4H-SiC/SiO₂ interfaces

Toru Akiyama¹, Tsunashi Shimizu¹, Tomonori Ito¹, Hiroyuki Kageshima², Kenta Chokawa³ and Kenji Shiraishi³

Published 25 March 2022 • © 2022 The Japan Society of Applied Physics

16 Total downloads

Turn on MathJax

Get permission to re-use this article

Share this article

Access this article

The computer you are using is not registered by an institution with a subscription to this article. Please choose one of the options below.

Login

Click

Access through your institution

Purchase from

Article Galaxy

CCC RightFind

Purchase this article from our

Rent from

Read this now at deepdyve

This article is available from

IOPscience login

② 「Find your Institution」に「Yamaguchi University」と入力して検索

IOPscience

Sign in to IOPscience

Enter "Yamaguchi University"

Find your institution

Yamaguchi University

Examples: Science Academy, sue@uni.ac.uk, London.

YU Yamaguchi University

③ 山口大学発行のアカウントでログイン

YAMAGUCHI UNIVERSITY 山口大学

— 学術認証フェデレーション —

ログインサービス: IOPscience

ユーザー名

Enter your YU ID/PW

パスワード

ログインを記憶しません。

送信する情報を再度表示して送信の可否を選択します。

Login

④ 認証完了
Authentication is completed